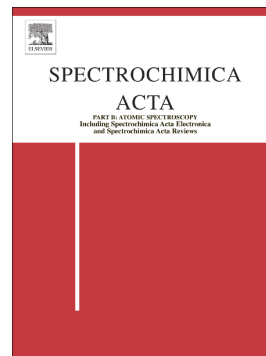


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Comparison of techniques for detecting metal contamination in silicon wafers

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